

## Nucleation and Crystal Growth of $\text{Zn}_{0.3}\text{In}_{1.4}\text{Sn}_{0.3}\text{O}_3$ (ZITO-30) Thin Films Studied by *in-situ* TEM

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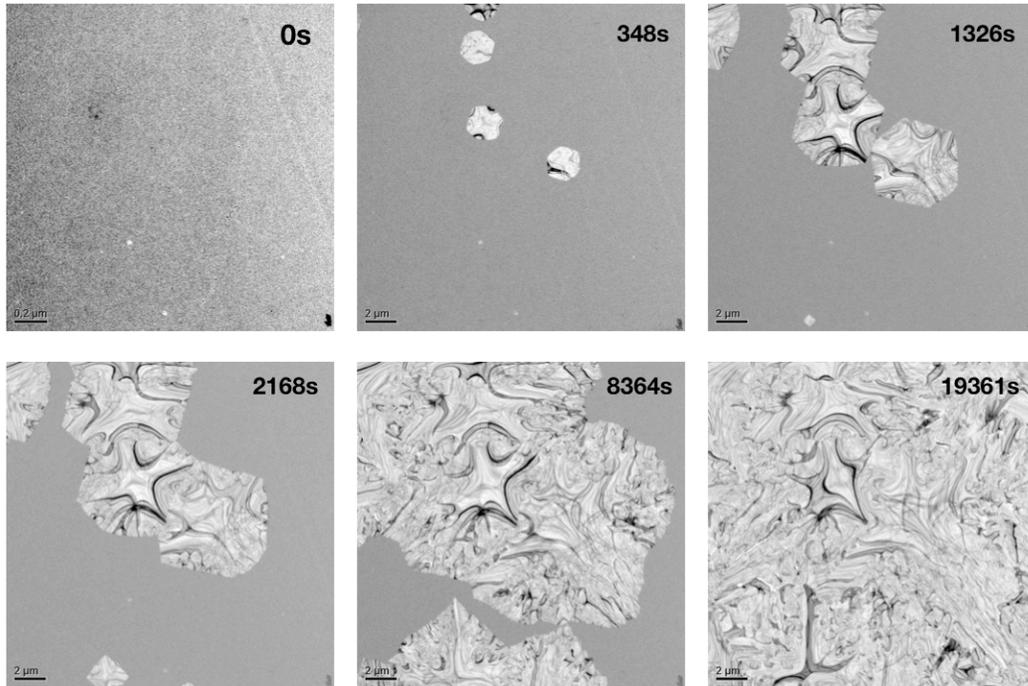
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Amorphous transparent oxide materials have been widely applied in various technologies, including UV detectors, fully transparent displays, integrated on-glass electronics, flexible electronics, and energy-conversion devices and systems [1]. Amorphous  $\text{Zn}_{0.3}\text{In}_{1.4}\text{Sn}_{0.3}\text{O}_3$ , in which 30% of the indium in the  $\text{In}_2\text{O}_3$  structure is replaced by co-substitution of zinc and tin, (a-ZITO-30) is one kind of the transparent oxide materials. The a-ZITO-30 thin films grown by Pulsed Laser Deposition (PLD) at different temperatures have different structures with short-range and medium-range ordering [2]. This underscores the need to unravel the nucleation and growth processes of a-ZITO-30 thin films and to understand the role of dopants in this process.

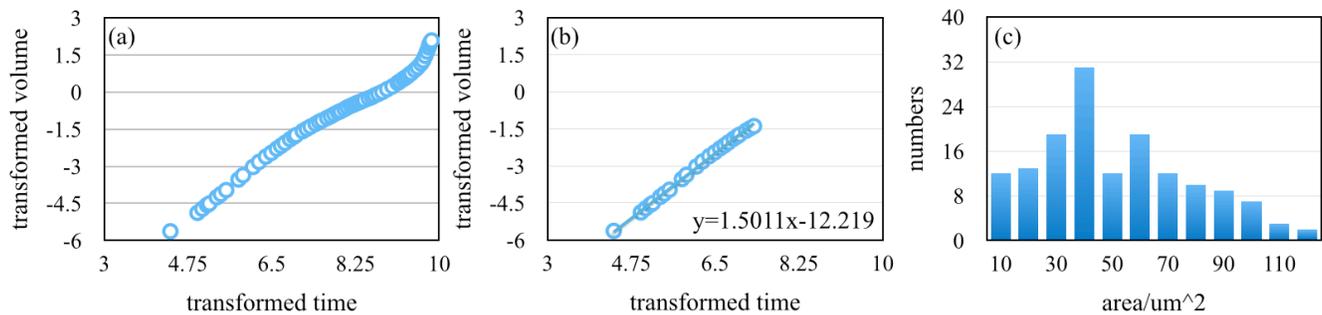
In order to monitor the microstructure evolution of a-ZITO-30 thin films, *in situ* heating experiments have been carried out inside a transmission electron microscope (TEM) to directly observe the crystal nucleation and growth process in real time [3]. The thin and amorphous films were heated at a constant temperature, causing the amorphous-to-crystalline transition (Figure 1), as seen with the appearance of bend contours. Such contours are typical contrast features for crystalline films under strain. Based on the Johnson-Mehl-Avrami-Kolmogorov (JMAK) theory [4], the kinetic crystal growth behavior of a-ZITO-30 thin film was also investigated. The deviation from JMAK theory (Figure 2. (a)) indicates that ZITO-30 thin films heterogeneously nucleate on the surface. The Avrami exponent derived from JMAK equation (Figure 2. (b)), as well as the large grain size distribution (Figure 2. (c)) calculated at a film thickness of about 50nm, agree with those predicted by a 2-D crystal growth mode. Furthermore, we studied the interface velocity, characteristic time and characteristic length for the nucleation process. When the holding temperature was raised from 355°C to 365°C, the interface velocity was found to increase from 0.46nm/s to 2.3nm/s. This suggests that energy barriers exist in the crystal growth system. With level-set simulation and inverse Wulff construction, nucleation mechanism as well as the anisotropic behavior of the system would be investigated. Combined with theoretical simulation, this *in-situ* TEM microstructural study will provide valuable insight for the design and synthesis of complex amorphous oxide semiconductor thin films with superior and unique optical, electrical, and thermal properties [5].

### References:

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- [2] Yan A *et al*, Journal of Applied Physics, 2012, 112(5): 054907.
- [3] Asoro, Michael A., Desiderio Kovar, and Paulo J. Ferreira, ACS nano 7.9 (2013): 7844-7852.
- [4] Proffit, Diana E. *et al*, Journal of Electroceramics 34.2-3 (2015): 167-174.
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**Figure 1.** Selected images showing the process of 2-D crystal growth with heterogeneous nucleation at a constant temperature of 365°C. The processing time is inserted.



**Figure 2.** Transformed volume fraction versus transformed time, (a) in the whole process, (b) in the first 1500 seconds with fitting equation inserted, Avrami exponent of 1.5 indicates 2-D crystal growth mode. (c) Grain size distribution of ZITO-30 thin films after annealing, showing microscale grain size.